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INFORMATION DISCLOSURE STATEMENT

Applicant: Shunpei YAMAZAKI et al.

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U.S. PATENT DOCUMENTS

Examiner Initial	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)
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	Document Number	Date	Country	Class	Subclass	Translation Yes No
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	61-80815	04/24/86	Japan			X
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	4-338631	11/25/92	Japan			X
	63-25933	02/03/88	Japan			X
	1-241862	09/26/89	Japan			X
	5-21339	01/29/93	Japan			X
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Examiner

miller, J. A.

Date Considered

September 26, 2001

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.